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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/609,236	06/26/2003	Venkat Selvamanickam	1014-SP106	7733
34456 7590 10/19/2007 LARSON NEWMAN ABEL POLANSKY & WHITE, LLP 5914 WEST COURTYARD DRIVE			EXAMINER	
			KACKAR, RAM N	
SUITE 200 AUSTIN, TX 78730		•	ART UNIT	PAPER NUMBER
			1792	
			MAIL DATE	DELIVERY MODE
	•		10/19/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)			
	10/609,236	SELVAMANICKAM ET AL.			
Office Action Summary	Examiner	Art Unit			
	Ram N. Kackar	1763			
The MAILING DATE of this communication Period for Reply	appears on the cover sheet w	ith the correspondence address			
A SHORTENED STATUTORY PERIOD FOR REI WHICHEVER IS LONGER, FROM THE MAILING  - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory per  - Failure to reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the may earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNION (1.136(a). In no event, however, may a notion will apply and will expire SIX (6) MON (1.14 tute, cause the application to become AB	CATION. reply be timely filed  NTHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on 9/	<u>/4/2007</u> .				
2a)⊠ This action is <b>FINAL</b> . 2b)☐ T	This action is <b>FINAL</b> . 2b) ☐ This action is non-final.				
3) Since this application is in condition for allo	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is				
closed in accordance with the practice unde	er <i>Ex par</i> te Quayle, 1935 C.D	). 11, 453 O.G. 213.			
Disposition of Claims	•	•			
4)⊠ Claim(s) <u>2,7-11 and 26-32</u> is/are pending in	the application.				
•	4a) Of the above claim(s) is/are withdrawn from consideration.				
5) Claim(s) is/are allowed.					
6) $\boxtimes$ Claim(s) <u>2,7-11 and 26-32</u> is/are rejected.					
7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction an	d/or election requirement.				
Application Papers					
9) The specification is objected to by the Exam	niner.				
10) The drawing(s) filed on is/are: a) a	accepted or b) objected to	by the Examiner.			
Applicant may not request that any objection to	the drawing(s) be held in abeya	nce. See 37 CFR 1.85(a).			
Replacement drawing sheet(s) including the cor	rection is required if the drawing	y(s) is objected to. See 37 CFR 1.121(d).			
11)⊡ The oath or declaration is objected to by the	Examiner. Note the attached	d Office Action or form PTO-152.			
Priority under 35 U.S.C. § 119					
12) ☐ Acknowledgment is made of a claim for fore a) ☐ All b) ☐ Some * c) ☐ None of:	ign priority under 35 U.S.C. {	§ 119(a)-(d) or (f).			
<ol> <li>Certified copies of the priority docum</li> </ol>	ents have been received.				
2. Certified copies of the priority docum		·· ——			
3. Copies of the certified copies of the p	•	received in this National Stage			
application from the International Bur					
* See the attached detailed Office action for a .	list of the certified copies not	received.			
Attachment(s)  1) Notice of References Cited (PTO-892)	4) 🔲 Interview	Summary (PTO-413)			
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Notice of Draftsperson's Patent Drawing Review (PTO-948)</li> </ol>	Paper No(	(s)/Mail Date			
3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	5)	Informal Patent Application			
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#### **DETAILED ACTION**

## Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 2, 7-11 and 26-32 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lijima et al (2001/0006042) in view of Vaidya et al (US 5076203).

Lijima et al disclose a process for cooling and positioning a translating substrate (tape like) which could be comprise metal like nickel (Paragraph 59) in a deposition chamber for vacuum deposition (abstract and Fig 3), gas inlet (38), source of deposition material (36), means of delivering the deposition material (ion beam -38), means of translating a substrate (24,25), means of positioning the substrate so that deposition material impinges on the substrate (23) whereas the substrate positioning means contains means to cool the substrate. Lijima et al further teach that the process is used for making a buffer layer of yttrium stabilized zirconia (YSZ) or MgO for a superconducting film (Abstract and paragraph 71) using ion assist (39).

Further Lijma et al teach that FWHM (full width at half maximum) is the measure of biaxial texture (*indicator of crystal orientation- Paragraph 99*) and that it could be minimum at an incidence angle of 50-60 degrees (paragraph 16,87 and 99). Further Lijima et al disclose various parameters affecting FWHM and disclose it to be below 10 degrees (Fig 13).

Lijima et al fails to teach that substrate positioning means contains internal gaseous coolant delivery channels and additional liquid coolant channels and specific size of gas orifices.

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Vaidya et al disclose a process for cooling and positioning a translating substrate in a deposition chamber for vacuum deposition (Col 1 lines 8-11, Col 2 lines 1-25), gas inlet (Fig 7-Fig 10), means of delivering the deposition material (electron –beam heater (Col 3 line 35), means of translating a substrate (Fig 6-22) from 0-90 meters per min (Abstract), curved means of positioning the substrate so that deposition material impinges on the substrate (23) whereas the substrate positioning means contains internal liquid coolant channels (23a and 23b) and internal gaseous coolant delivery channels (Fig 6-30, Fig 7-Fig10 and Col 6 lines 5-68) which could use oxygen or argon to allow the temperature from 0° C upwards.

As discussed above Vaidya et al disclose the substrate positioning means contains internal liquid coolant channels (23a and 23b) and internal gaseous coolant delivery channels from behind the support either through porous fixed support (Fig 7- Fig10 and Col 6 lines 5-20) or through an enclosed cavity (Fig 7-10 and Col 6 lines 44-68).

Furthermore, Vaidya et al teach that these features could be combined (Col 6 lines 44-68) and teach that the injection holes could be 1.5 mm diameter at 15 mm pitch (Col 4 lines 3-9).

Vaidya et al teach that the gaseous delivery behind the web substrate reduces friction in addition to provide cooling by conduction of heat between the substrate and the cooled support (Col 4 lines 37-55).

Therefore having gaseous delivery behind the web substrate to reduces friction in addition to provide cooling by conduction and convection means and provision of liquid coolant channels in IBAD apparatus would have been obvious to one of ordinary skill in the art at the time of invention in order to remove the heat from the positioning means and reduce friction to enable higher web speed.

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Since the hole diameter and spacing determine the amount of gas and its distribution behind the substrate which affects amount and uniformity of cooling it would have been obvious for one of ordinary skill in the art at the time of invention to replace the porous outlets in the support by spaced holes to distribute sufficient gas behind the tape substrate for optimum heat transfer and reduced friction.

Regarding the gas channels extending to the first surface and being hollow and open along an entirety of said length, Fig 7-Fig 10 show gas channels, which extend to the first surface through the pores in the porous material since they allow the flow to reach the first surface. It is inherent that the pores work because they are connected to each other continuously up to the surface and they must be hollow to allow the flow to take place.

It is noted that pores and tubular channels are equivalent and function in the same way.

## Response to Arguments

Applicant's arguments filed 9/4/2007 have been fully considered but they are not persuasive.

The applicant argues that Vaidya et al fail to disclose gas channels open to the deposition chamber. This is incorrect since gases exit through numerous channels through the porous media.

### Conclusion

3. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ram N. Kackar whose telephone number is 571 272 1436. The examiner can normally be reached on M-F 8:00 A.M to 5:P.M.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on 571 272 1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Ram Kackar

Primary Examiner AU 1763